Annealing in n and p-side readout of silicon microstrip detectors after irradiation to LHC and sLHC doses

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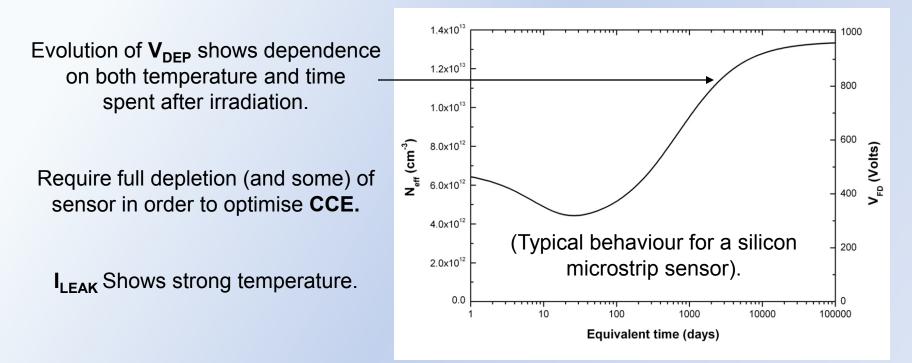


CONTEXT:

Two rather recent results from studies performed for preparing high resolution sensors for the future supercolliders (sLHC at CERN) have proven that silicon detectors can be used for tracking minimum ionising particles (mip's) after doses above 2x10¹⁶ n_{eq} cm⁻². These are the discovery of the charge multiplication mechanism taking place in irradiated **n-in-p** silicon detectors and the suppression of the reverse annealing. A discussion of this last feature is here presented with the implications for the running scenario in the actual experiments.

Evolution of Sensor Properties After Irradiation

Sensor leakage current (I_{LEAK}) , depletion voltage (V_{DEP}) and charge collection efficiency (CCE) are all affected by irradiation.



Need to avoid the sensors being warm (> 0 °C) for long periods of time!

Comparison of Hamburg Model and ATLAS TDR Parameterisation

The Hamburg parameterisation is believed to best fit the available data to predict V_{DEP} .

However, large differences observed between the predictions of the TDR model and the Hamburg model.

Origin is in **reverse annealing** contribution ΔN_Y to the predicted change in effective doping concentration ΔN_{EFF} :

$$\Delta N_{EFF} (\Phi, T, t) = \Delta N_{C} (\Phi) + \Delta N_{A} (\Phi, T, t) + \Delta N_{Y} (\Phi, T, t)$$

$$V_{DEP} = \frac{ed^{2} |N_{EFF}|}{2\varepsilon}$$

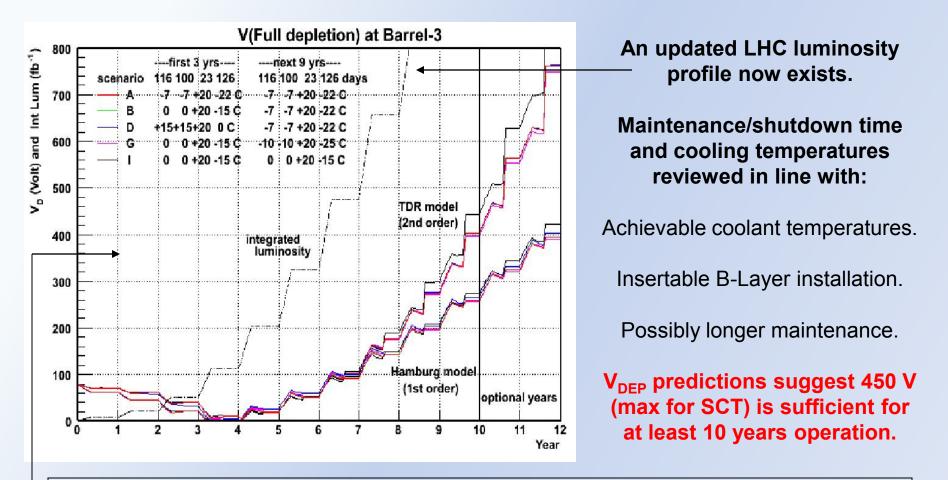
TDR model parameterised reverse annealing as a **second order process** $(dN_{Y}=-k\cdot dN_{X}^{2}\cdot dt) \quad N_{Y}(t)=N_{X,0}(1-(1+k\cdot N_{X,0}\cdot t)^{-1}).$

Hamburg model parameterises reverse annealing as a modified first order process.

 $(dN_{Y}=-1/\tau \cdot dN_{X} \cdot dt) N_{Y}(t)=N_{X,0}(1-exp(-t/\tau))$

Need high fluence + long annealing data to compare to predictions of both models.

Re-Evaluating the Evolution of V_{DEP} and I_{LEAK} in the SCT



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Programme of Accelerated Annealing Measurements

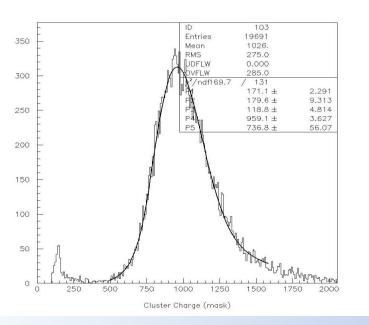
Sensor performance traditionally studied by determining V_{DEP} from CV measurements. The rate of annealing is a function of temperature, therefore it is possible to slow it down or accelerate it relatively to a given temperature. Previous studies have found an Arrhenius relation for temperature dependence of the reverse annealing of V_{DEP} with an activation energy Ea = 1.31 eV. With a reference temperature of 20°C, the acceleration factors are about 540 at 60°C and 7350 at 80 °C.

In Liverpool the focus has been on measuring the annealing of CCE The p-in-n case.

New programme of accelerated annealing measurements on ATLAS mini sensors .	Manufacturer	HPK
	Wafer Tech.	FZ
Pair of sensors irradiated with neutrons at Ljublijana (V. Cindro et al) to 2x10¹⁴ 1 MeV n_{eq} cm⁻²	Structure	p-in-n
	Size	1 cm x 1 cm
(new prediction for SCT = 1.6x10 ¹⁴ 1 MeV n_{eq} cm⁻²).	Thickness	285 µm

One sensor used for CCE measurements and one sensor used for V_{DEP} measurements. Both **sensors annealed together** at same temperature for same length of time.

Experimental Setup and Analysis Procedure

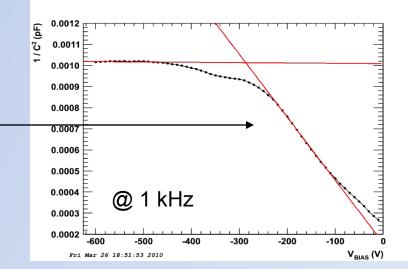


Charge Collection Measurements

⁹⁰Sr fast electron source used to generate signal. Readout triggered by scintillator.

 Charge collection measured using analogue electronics chip (SCT128A or Beetle) clocked at LHC speed (40 MHz clock, 25 ns shaping time).

System calibrated to most probable value of MIP energy loss in non-irradiated 300 μ m thick sensor (~ 23000 e).

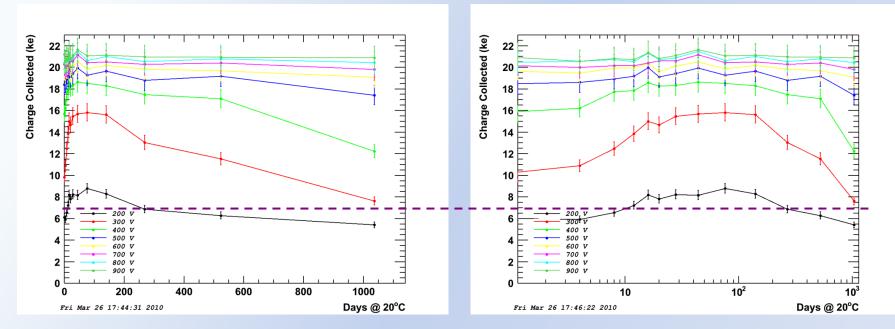


Depletion Voltage Measurements

 V_{DEP} Determined by standard method of measuring the V_{BIAS} at which 1/C² saturates.

Both sets of measurements performed in freezer at temperature of ~-25 °C with N² flush.

Results of Charge Collection Measurements



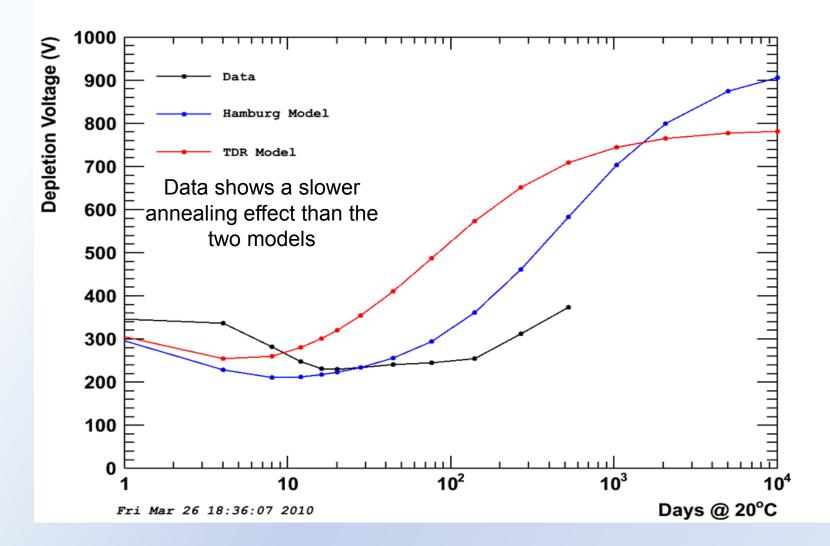
Above ~ 500 V collected charge remains almost constant in time

SCT Default threshold 1 fC (~ 6.2 ke)

No sharp drop in the collected charge

Smooth fall off after ~ 100 days @ 20 °C

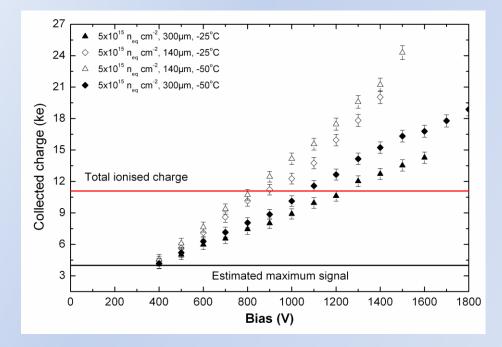
Comparison of Predicted V_{DEP} and Measured V_{DEP}



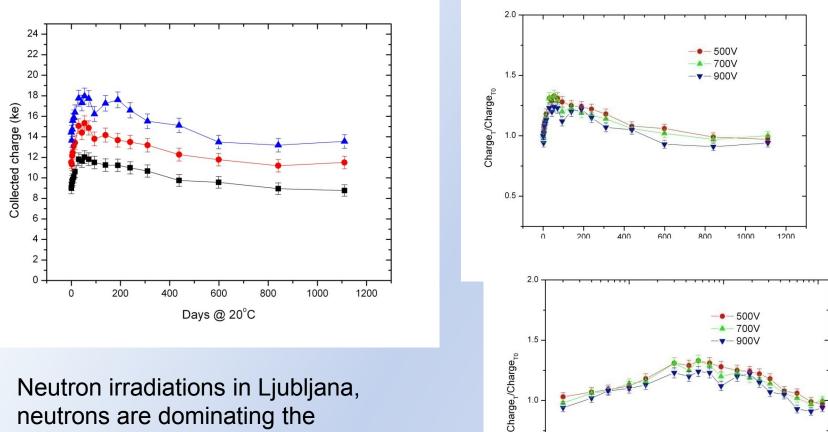
This discussion is relevant to the present tracker sensors in the LHC experiments. The future experiments on sLHC will make large use of n-side readout sensors, possibly n-in-p. The annealing of n-in-p sensors is different again: the reason is that the effect of charge multiplication plays a role.

140 and 300 μ m n-in-p Micron microstrip sensors after 5x10¹⁵ n_{eq} 26MeV p

Evidence of a charge multiplication effect: not only the whole charge is recovered, but increased by f = 1.75/2.1



Accelerated Annealing of the collected charge, case of n-in-p sensors. HPK FZ <u>n-in-p</u>, 1E15 n_{ea} cm⁻²



neutrons are dominating the radiation damage > 25 cm radius.

G. Casse, 17th RD50 Workshop, CERN 17-19 Nov.2010

0.5

10

100

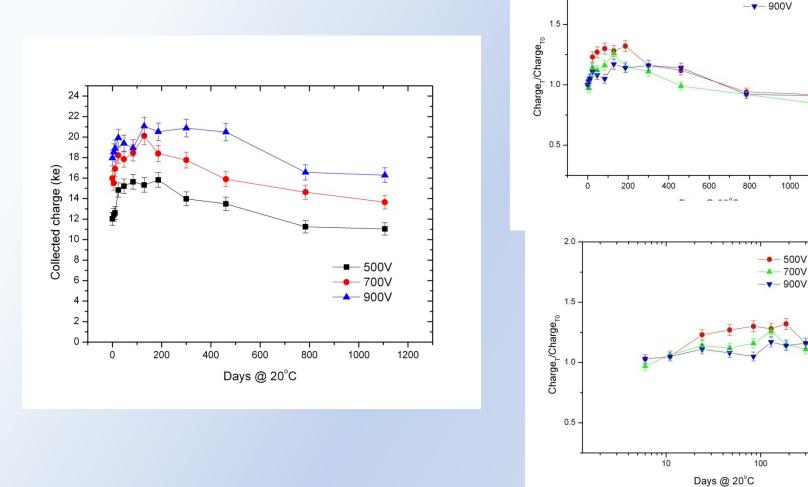
Days @ 20°C

1000

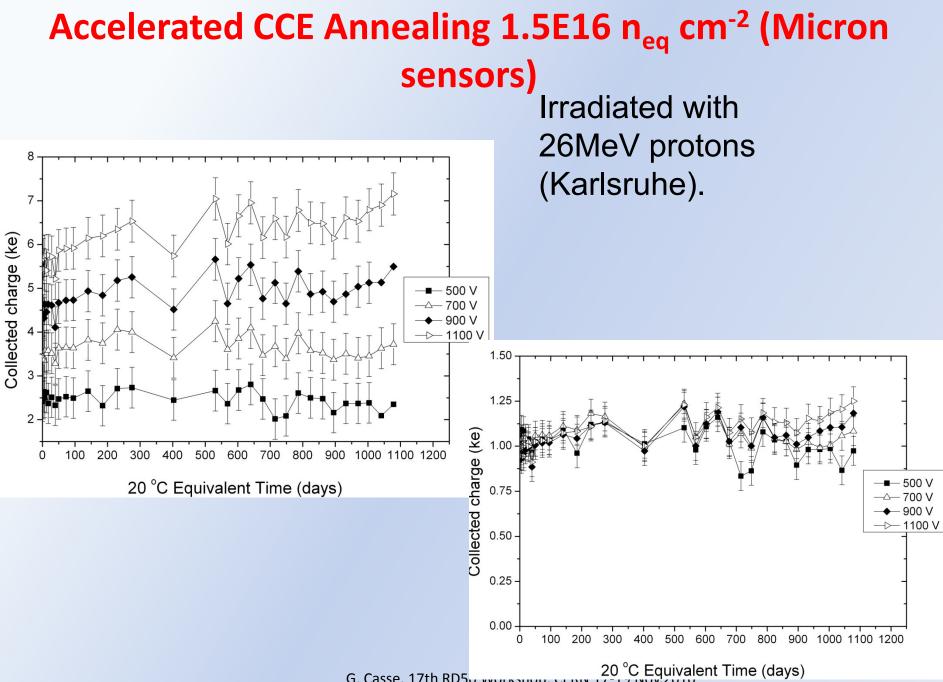
Annealing of the colleted charge, Micron FZ n-in-p, 1E15 n cm⁻² (26MeV p irradiation)

2.0

1200

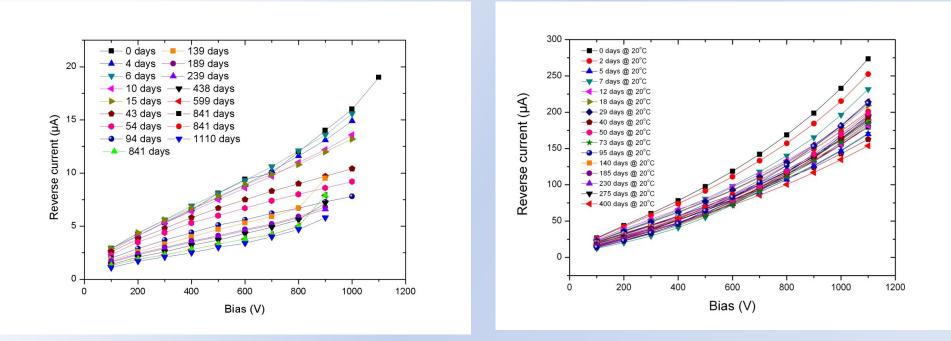


G. Casse, 17th RD50 Workshop, CERN 17-19 Nov.2010 1000

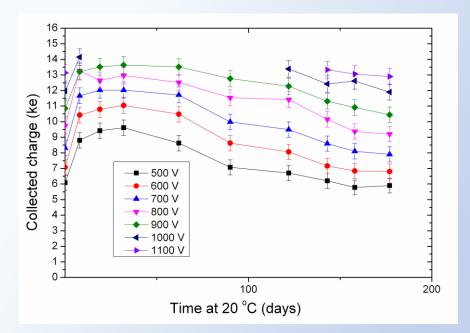


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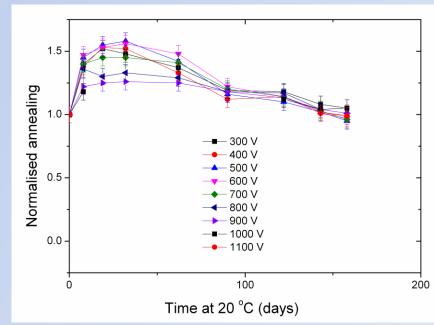
Annealing of the reverse current, n-in-p sensors, 1E15 and 1.5E16 n cm⁻²



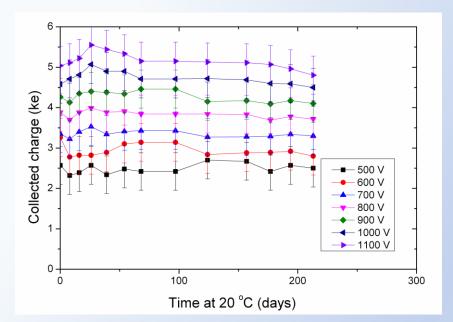
Room Temperature Annealing of the collected charge, HPK FZ n-in-p, 2E15 n cm⁻² (26MeV p irradiation)



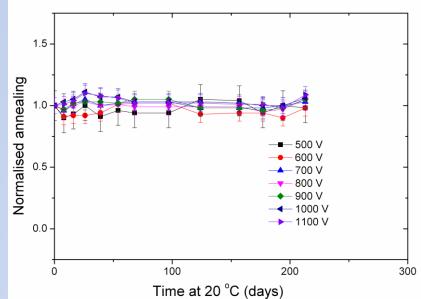
We make large use of accelerating annealing: is this a safe and correct approach?



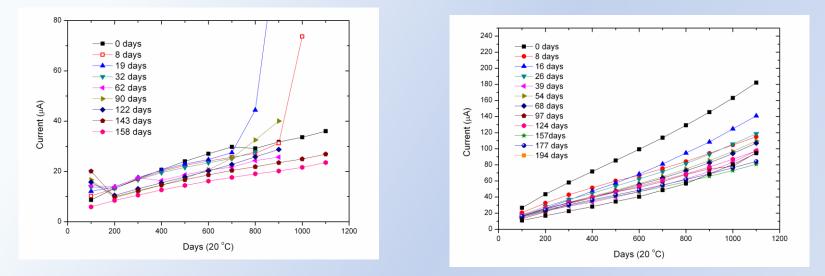
Room Temperature Annealing of the collected charge, HPK FZ n-in-p, 1E16 n cm⁻² (26MeV p irradiation)

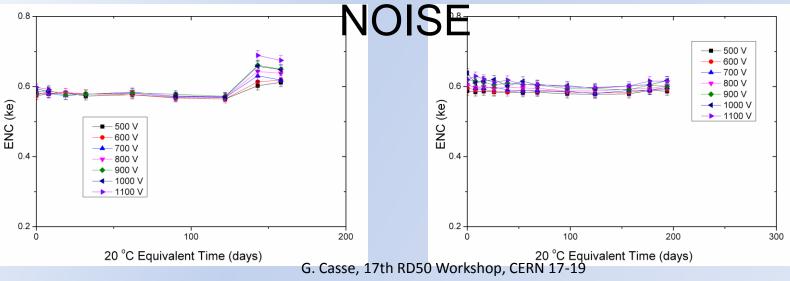


We make large use of accelerating annealing: is this a safe and correct approach?



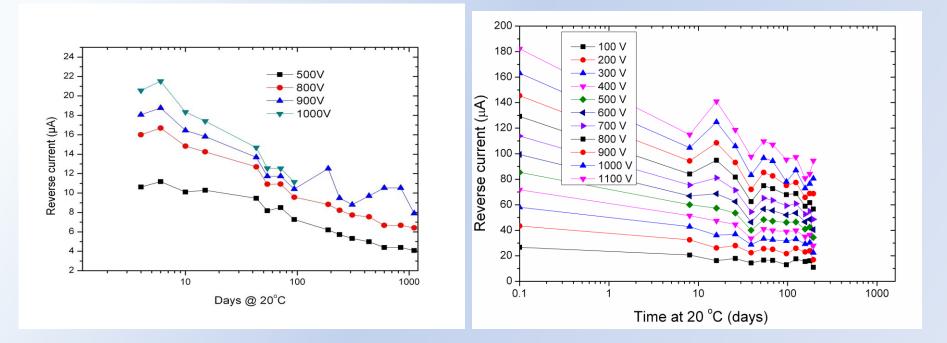
Room Temperature Annealing of the reverse current, n-in-p sensors, 2 and 1E16 n cm⁻² (26MeV p irradiation)





Nov.2010

Comparison of the Accelerated and Room Temperature Annealing of the reverse current, HPK FZ n-in-p, 2E15 and 1E16 n_{eq} cm⁻²



CONCLUSIONS

- The CCE measurements with both p-in-n and n-in-p sensors show discrepancies with accepted annealing features as measured with CV methods and as predicted by widely accepted parameterisations. In practical terms, the changes with annealing of the CCE sensors after LHC doses (microstrip sensors) are less severe than anticipated.
- With n-in-p sensors the reverse annealing seems suppressed when the study is performed by accelerating the annealing at 60 and 80 °C (maximum voltage 1100V). Nonetheless the rescaling of the accelerated annealing to RT could be wrong at least when applied to the CCE. The reason could be the rescaling criterion itself, or a different evolution of the effective space charge triggered by temperatures between 20 and 60-80 °C.
- Controlled annealing (at 20^oC) is still a very useful tool to reduce power dissipation and recover fraction of S/N in heavily irradiated silicon detectors. The discrepancies between the accelerated and RT annealing need to be studied to base the prediction for the changes of CCE with time according to the real operation and maintenance temperatures in the experiments.